到

Notice of Allowability	Application No.	Applicant(s)	
	10/735,845	YANG ET AL.	
	Examiner	Art Unit	
	Thanh Y. Tran	2822	
The MAILING DATE of this communication appears on the cover sheet with the correspondence address All claims being allowable, PROSECUTION ON THE MERITS IS (OR REMAINS) CLOSED in this application. If not included herewith (or previously mailed), a Notice of Allowance (PTOL-85) or other appropriate communication will be mailed in due course. THIS NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGHTS. This application is subject to withdrawal from issue at the initiative of the Office or upon petition by the applicant. See 37 CFR 1.313 and MPEP 1308.			
1. This communication is responsive to <u>1/4/07</u> .			
2.  The allowed claim(s) is/are <u>1, 3-11, and 24-29</u> .			
<ul> <li>3. Acknowledgment is made of a claim for foreign priority una)</li> <li>All b) Some* c) None of the:</li> <li>1. Certified copies of the priority documents have</li> <li>2. Certified copies of the priority documents have</li> <li>3. Copies of the certified copies of the priority documents have</li> <li>International Bureau (PCT Rule 17.2(a)).</li> <li>* Certified copies not received:</li> </ul>	been received. been received in Application No		ition from the
Applicant has THREE MONTHS FROM THE "MAILING DATE" of this communication to file a reply complying with the requirements noted below. Failure to timely comply will result in ABANDONMENT of this application.  THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.			
4. A SUBSTITUTE OATH OR DECLARATION must be submitted. Note the attached EXAMINER'S AMENDMENT or NOTICE OF INFORMAL PATENT APPLICATION (PTO-152) which gives reason(s) why the oath or declaration is deficient.			
5. CORRECTED DRAWINGS ( as "replacement sheets") must be submitted.			
(a) ☐ including changes required by the Notice of Draftsperson's Patent Drawing Review ( PTO-948) attached			
1) hereto or 2) to Paper No./Mail Date			
(b) ☐ including changes required by the attached Examiner's Amendment / Comment or in the Office action of Paper No./Mail Date			
Identifying indicia such as the application number (see 37 CFR 1.84(c)) should be written on the drawings in the front (not the back) of each sheet. Replacement sheet(s) should be labeled as such in the header according to 37 CFR 1.121(d).			
6. DEPOSIT OF and/or INFORMATION about the deposit of BIOLOGICAL MATERIAL must be submitted. Note the attached Examiner's comment regarding REQUIREMENT FOR THE DEPOSIT OF BIOLOGICAL MATERIAL.			
Attachment(s)  1. Notice of References Cited (PTO-892)  2. Notice of Draftperson's Patent Drawing Review (PTO-948)  3. Information Disclosure Statements (PTO/SB/08), Paper No./Mail Date  4. Examiner's Comment Regarding Requirement for Deposit of Biological Material	5. ☐ Notice of Informal P 6. ☑ Interview Summary Paper No./Mail Da 7. ☐ Examiner's Amenda 8. ☑ Examiner's Stateme 9. ☐ Other	(PTO-413), te ment/Comment	owance
	•		

Application/Control Number: 10/735,845

Art Unit: 2822

## **DETAILED ACTION**

## Allowable Subject Matter

- 1. Claims 1, 3-11, and 24-29 are allowed.
- 2. The following is an examiner's statement of reasons for allowance:

The prior art of record and to the examiner's knowledge does not teach or render obvious, at least to the skilled artisan, the instant invention regarding a method of making an interconnect structure comprising: an interlayer dielectric having a trench and a via; a cap layer is in contact with an interconnect copper line in a dielectric trench; wherein a portion of the cap layer and the sacrificial layer are removed from the bottom surface of the via so that the removed portions of the cap layer and the sacrificial layer deposit predominantly along the lower sidewalls of the via, as defined in claim 1. Claims 3-11 are dependent upon independent claim 1.

The prior art of record and to the examiner's knowledge does not teach or render obvious, at least to the skilled artisan, the instant invention regarding a method of making an interconnect structure comprising: an interlayer dielectric having a trench and a via; a cap layer is in contact with an interconnect conductive line in a dielectric trench; wherein a portion of the cap layer and the sacrificial layer are removed from the bottom surface of the via so that the removed portions of the cap layer and the sacrificial layer deposit predominantly along the lower sidewalls of the via, as defined in claim 24. Claims 25-29 are dependent upon independent claim 24.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Art Unit: 2822

## Contact Information

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Thanh Y. Tran whose telephone number is (571) 272-2110. The examiner can normally be reached on M-F (9-6:30pm).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Zandra Smith can be reached on (571) 272-2429. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

**TYT** 

Zandra V. Smith

Supervisory Patent Examiner 200 T